Julius-Maximilians-UNIVERSITÄT WÜRZBURG



Quantum transport measurements on Bi₂Se₃ topological insulators

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Motivation



Spintronic = Spin based electronics

- "Classical" Spintronic
 - Use of electron spin in conventional hard disks
 - GMR Giant Magneto Resistance effect



Conventional Hard disk [CHJ]

- "Modern" Spintronic
 - Spin currents
 - Spin transistor



Spin Field Effect transistor [IHT]



Introduction



"Insulator" :

Band gap between valence- and conduction band

"Topological" :

Conducting spin-split 1D (2D) edge states within the band gap

Topological Insulators are conducting!



Simple band structure [HK10]



Topological Insulators



Analogy:

Quantum Spin Hall Effect \approx superposition of 2 counter-orientated QHE



Topological Insulator:

"Internal" magnetic field caused by spin-orbit interaction!



Band structure Bi₂Se₃



Spin-orbit interaction causes band inversion at the Brillouin zone center $\boldsymbol{\Gamma}$



Ab initio calculations of Bi_2Se_3 surface states [SZ09]



Valence- and conduction band at Γ including following effects:
(I) Chemical bonding
(II) Crystal field distortion
(III) Spin-orbit coupling
[SZ09]



Bi₂Se₃ ARPES measurements



2009 ARPES measurements: Bi_2Se_3 is topological insulator!

BUT!

Destinct topological properties not useable!



ARPES data Bi_2Se_3 2009 [HH09]

Goal:

- Preparation of non (bulk) conducting Bi₂Se₃ crystals
- Quantum transport measurements on surface states

Why Bi₂Se₃?

• Large E_{gap} – Room temperature spintronic applications



Crystal structure Bi₂Se₃



Problems:

n-type doping by crystal defects



(a) Unit cell Bi_2Se_3 (b) On top view (c) Cross section [SZ09]

Causes:

- Se vacancies (+2 e-)
- Bad growth start cause layer of poor crystal quality



TEM substrate interface [TM12]



Sample preparation and layout





Lithography process diagram



Top-view without gate



Sample bonded to carrier

Preparation and layout:

- Made from Bi₂Se₃ (Si/InP substrate) Wafer piece
- Sample preparation by means of photolithography
- 2 Hall bar layout (600 x 200) μm und (10 x 30) μm

Transport setup



Setup:

WL

- ⁴He cryostat
- T = 4.2 K
- Superconducting magnet
- B_{\perp} field up to 14 T
- DC measurements



Circuit diagram [MR11]



"14T"- Setup Ep3 Wuerzburg



Samples on Silicon substrate



Samples on Silicon :

- **High densities**
- Low mobilities
- **Bulk conductance** •

Lattice constants:

- $a_{Si(111)} = 3.84 \text{ Å}$ $a_{Bi_2Se_3(111)} = 4.14 \text{ Å}$
- $a_{InP(111)} = 4.15$ Å



InP substrate

7%



BiSe 295



Samples on InP + Fe, annealed



Samples on InP :

- Lower densities •
- **Higher mobilities**
- Non linear Hall
- 2 different carriers





Large domains visible in AFM images High sample quality

BiSe 374



High field measurements



The Bi₂Se₃ thickness of 190 nm is >> 2D system, therefore:



Bitter-magnet HMFL Nijmegen

UNI WÜ

Magnetic field rotation



True 2D electron gas:

- Oscillations independent of B_{||} component!
- Oscillations periodic in 1/B
- Only holds up to 50^o Oscillations only in some cases periodic in 1/B
- Oscillations caused by other effects?
- Multiple oscillation frequencies?









Goals:

- Growth of bulk insulating Bi₂Se₃
- Quantum transport measurements of 3D TI surface states

Results:

- Improvement of carrier density and carrier mobility
- Established growth on InP substrates
- High field measurements: Surface states or bulk oscillations (!?)

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Thank you for your kind attention!







- [HK10] Z. Hasan, L. Kane. *Colloquium: Topological Insulators,* Review of modern physics, vol. 82, 2010
- **[SZ09]** S. C. Zhang et al. *Topological insulators in Bi2Se3, Bi2Te3 and Sb2Te3 with a single Dirac cone on the surface*. Nature Physics, 5:438, 2009.
- [MR11] M. Reuß. *Transporteigenschaften dreidimensionaler topologischer Isolatoren*, Diplomarbeit, Physikalische Fakultät Universität Würzburg, 2011.
- [HH09] M. Hasan, D. Hsieh et al. *A tunable topological insulator in the spin helical Dirac transport regime,* Nature vol. 460, 2009
- **[TM12]** N. Tarakina, L. Molenkamp et al. *Comparative Study of the Microstructure of Bi2Se3 Thin Films Grown on Si(111) and InP(111) Substrates,* Crystal Growth and Design, 2012
- [CHJ] C. Jansky, public domain, wikipedia.org/festplatte.
- [IHT] Institut für Halbleitertechnik, Universität Köln, iht.uni-stuttgart.de/forschung/spinplasm



Band structure Bi₂Se₃





Ab initio band simulations: (a) without SOC (b) with SOC



Topological Insulators



Time reversal symmetry maintained since ky $B_{Total} = 0 !$ k_x K K **Conduction Band** Ε Conduction Band (a) E (b) E, EF Valence Band Valence Band Га k Гb Га k Γ_{b} [HK10] 3D: $(-1)^{\nu_0} = \prod_{i=1}^8 \delta(\Gamma_i)$ Γ_i : Kramers degenerate points [HK10]

- (a) No topological insulator at even number of intersections
- (b) \mathbb{Z}_2 topological insulator at $\Delta v_0 = Nmod2 = 1$



Photolithography





Lithography process diagram



Transport measurements



1 Carrier model:

$$A_{H} = \frac{1}{nq} \qquad n = \frac{1}{ed} \frac{I}{U_{H}} B = \frac{1}{ed} \frac{B}{R_{H}} \qquad \mu = \frac{\sigma}{ne} = \frac{l}{R_{xx}b} \frac{R_{H}}{B}$$

2 Carrier model:

$$A_{H} = \mp e^{-1} \frac{(\mu_{1}^{2}n_{1} + \mu_{2}^{2}n_{2}) + (\mu_{1}\mu_{2}B)^{2}(n_{1} + n_{2})}{(\mu_{1}|n_{1}| + |n_{2}|)^{2} + (\mu_{1}\mu_{2}B)^{2}(n_{1} + n_{2})^{2}}$$

- Determination of transport parameters via Hall measurements
- Fit 1 or 2 carrier model to data

Topological Insulators



Quantum Hall Effect:

WU

$$\varepsilon_m = \hbar \omega_c \left(m + \frac{1}{2} \right)$$

 $\sigma_{xy} = N \frac{e^2}{h}$

Hall constant can be calculated From the Berry flux

$$N = \sum_{m} n_{m}$$

$$n_{m} = \int d^{2} \mathbf{k} \left(\nabla \times \left(i \langle u_{m} | \nabla_{k} | u_{m} \rangle \right) \right) \qquad I = \frac{\Delta F}{\Delta \Phi} = \frac{n e(\mu_{a} - \mu_{i})}{h} \qquad G = \frac{I}{U} = n \frac{e^{2}}{h}$$

Laughlin Picture:





Samples on ZnCdSe buffer



BiSe 353 100 Samples with ZnCdSe buffer: 990 ZnCdSe Buffer auf InP 80 d = 50 [nm]**Better densities** 980 60 **Higher mobilities** R_xx [Ohm] R_xy [Ohm] 970 40 n_{3d} = 6.6E18 [1/cm^3] 20 n_{2d} = 3.3E13 [1/cm^2] 960 **Draw backs:** $\mu = 592 [cm^2/Vs]$ σ = 62959 [1/(Ohm*m)] 0 950 **Difficult growth** -20 2 3 5 0 1 4 -1 New error types B [T]

Samples on InP + Fe, miscut



[TM12]

Mag = 80.00 K X

Iron doped InP substrate:

- InP insulating
- Better carrier densities
- Higher mobilities (compared to Si(111))



EHT = 2.00 k

WD = 3.1 mm

Signal A = InLens

File Name = BiSe358-33.t

Miscut:

- Surface miscut relative to InP(111)
- Idea: stepwise growth



Fourier transformation



2 frequencies = 2 surface states ?

- Hard to get carrier densities from few oscillations
- Signal to weak for FFT





Temperature dependence



